Review of Frontier Workshop and Q-slope results

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12th SRF Workshop, July 10th-15th 2005, Cornell

Workshop on Pushing the Limits of RF Superconductivity

- September 22-24, 2004
- Hold at Argonne National Laboratory
- 64 participants invited to discuss how to push the limits of RF superconductivity for particle accelerators
- 30 talks divided in three sessions:
 - Ultimate field limits, new materials, new geometries
 - High Q, field emission, Q-slopes
 - Future research paths to ultimate performance

Workshop's website: http://www.aps.anl.gov/conferences/RFSC-Limits/



Workshop's presentations available on-line

(http://www.aps.anl.gov/conferences/RFSC-Limits/Presentations.html)

Workshop's proceedings published as Argonne Report ANL-05/10, March 2005

Outline

- Overview of knowledge on high field Qslope (or "Q-drop")
- Improved oxygen diffusion model and possible explanation of Q-drop
- Summary

Q-drop: obstacle before the ultimate limit



BCP treated cavities (1)

Fine grain (~ 50μm), rough surface (5-10μm)



Q-drop STILL PRESENT after baking

BCP treated cavities (2)

 Larger grains (1-5mm) by post-purification, rough surface (5-10μm)



BCP treated cavities (3)

"Air" baking



- Reduced Q-drop improvement
- Higher residual resistance

EP treated cavities (1)

• Fine grain (~ 50μ m), smooth surface (2- 5μ m)



EP treated cavities (2)

 Larger grains (~ 1mm) by post-purification, smooth surface (2-5μm)



Single grain BCP cavities

• One grain, very smooth surface (<1 μ m) with BCP



P. Kneisel et al.-PAC 05-TPPT076

Statistic on Q-drop onset field



Conclusions (1)

- Q-drop is common to BCP, EP and Single crystal cavities
- The onset field is ↑ the ↓ the density of grain boundaries is
- The baking effect is different on polycrystalline "fine grain" Nb treated by BCP and EP, but is similar for ↓ density of grain boundaries
- "Air" baking less effective than "UHV" bake

Origin of Q-drop: E- or B-field?

 Interface Tunnel Exchange Model¹: resonant absorption of energy due to tunneling of normal e⁻ between metal and oxide in the presence of strong Efield

$$R_{S}^{E} = b \left[exp(-c/E_{rf}) - exp(-c/E_{0}) \right]$$

Excellent fit to experimental data

All other models^{2,3,4,5}: Q-drop is a magnetic field effect

¹J. Halbritter, IEEE Trans. on Appl. Superc., 11 No. 1 (2001) 1864

- ²K. Saito, Proc. 11th SRF Workshop, Travemuende, Germany (2003), ThP17
- ³A. Gurevich, Argonne Report ANL-05/10, (2005) p. 17
- ⁴H. Safa, *Proc. 10th SRF Workshop*, Tsukuba, Japan (2001) p. 279
- ⁵J. Knobloch et al., *Proc. 9th SRF Workshop*, Los Alamos, NM (1999) p. 77

Measurements on TE₀₁₁ mode



G. Ciovati and P. Kneisel – Frontier Workshop – p. 74

After post-purification, Q-drop appears in TE_{011} mode (zero E-field on surface) with the same field dependence as for TM_{010} mode and recovers after baking

HF treatment

• HF used to remove oxide layer after baking. The surface is being re-oxidized after rinsing and air exposure



B. Visentin – Frontier Workshop – p. 94

Q-drop is NOT restored after a new oxide layer is formed

Temperature maps before baking



"Patchy" losses develop at the cavity equator (high magnetic field region)

Conclusions (2)

- The Q-drop is due to high magnetic field
- The benefit of baking is maintained after
 - exposure to air for 3 years
 - high pressure water rinsing
 - build-up of new oxide layer





- Decrease of R_{BCS} due to strong \downarrow of l and slight \uparrow of energy gap
- The physics of the niobium surface changes from CLEAN (l > 200 nm) to DIRTY LIMIT ($l \approx 25$ nm $\cong \xi_0$) ¹⁹

Surface studies on samples

- Natural oxide (Nb_2O_5) decomposes into sub-oxides (NbO, NbO_2) , thinner oxide layer
- Segregation of interstitial oxygen near metal-oxide interface, measured conc. up to 10 at.%
- Hydrogen? Very difficult to measure accurately, no clear data yet



C. Antoine – Frontier Workshop – p. 65

How deep is the baking benefit?



Red squares – additional 30 V/60 V anodizing Blue circles – BCP + 100 C baking

H. Padamsee et al. - Frontier Workshop - p. 293

Cavity test result: original Q-drop is obtained after ≈ 20 nm thick Nb was converted to oxide Sample analysis: oxygen concentration in 20 nm depth reduced by baking

Susceptibility meas. on samples

- r_{GL} (Ginzburg-Landau) =1.695
- In these measurements: r₃₂ >1.8

Two possible explanations:

- $B_{c2}^{surf} > B_{c2}^{bulk}$ $B_{c3} = r_{GL} B_{c2}^{surf}$ ("naïve" model)
- impurities in a layer $d \le \xi$ $r_{32}=1.67[1+(1-\chi_G)\sqrt{1.7} d/_x]$ $\uparrow T_{bake}$, time: $\uparrow d, \downarrow l$

 $r_{32}=B_{c3}/B_{c2}$: depends on bake temperature and duration



Magneto-optical meas. on samples

• Study flux penetration in Nb samples



Optical image, large grain sample (by post-purif.) BCP treated



MO image at 57 mT, 7 K

Evidence of flux penetration along grain boundaries!

P. J. Lee et al. - Frontier Workshop - p. 84

Conclusions (3)

- Impurity diffusion occurs during baking
 - Decrease of mean free path (cavity meas.)
 - Susceptibility measurements (samples)
 - XPS analysis (samples)
- High O concentration near the surface (≈20nm deep) reduced by baking
- Flux penetration may occur at grain boundaries



Oxygen diffusion models

Solve diffusion equation



S. Calatroni et al. - SRF 01 - PR025

H. Safa – SRF 01 – MA008

Improved model

Contribution from dissociation of oxide layer

 $Nb_2O_5 \xrightarrow{k} NbO \qquad k(T) = Ae^{-E_a/RT} \quad A \cong 3 \times 10^9 \text{ 1/s} \quad E_a \cong 135 \text{ kJ/mol}$



Solution:

$$u(x,t) = \frac{u_0}{\sqrt{\pi D(T)}} \int_0^t \frac{k(T)e^{-k(T)s}}{\sqrt{t-s}} e^{-\frac{x^2}{4D(T)(t-s)}}$$

Concentration of oxygen produced by the oxide reduction

 \cong 1000 at.% nm, obtained from comparison with data

B. R. King *et al.*, Thin Solid Films 192, p. 351 (1990)

 Diffusion of interstitial oxygen existing before baking

$$\frac{\partial v(x,t)}{\partial t} = D(T)\frac{\partial^2 v(x,t)}{\partial x^2} \qquad v(0,0) = v_0$$

Solution:

$$v(x,t) = \frac{v_0}{\sqrt{4\pi D(T)t}} e^{-\frac{x^2}{4D(T)t}}$$

 $\approx 10 \text{ at.\% nm}$ I. Arfaoui *et al.*, J. Appl. Phys. 91,
p. 9319 (2002)

General solution:

$$c(x,t) = u(x,t) + v(x,t)$$

Comparison with data



Data are from: P. Kneisel – SRF 99 - p. 328

Oxygen concentration at the surface as function of baking temperature



Optimum baking temperature: lowers O conc. near the surface

Schematic of the Nb surface

Before baking

After baking





How is O related to the Q-drop?



[#] C.C. Koch *et al.*, Phys. Rev. B 9 (1974) p. 888

Flux penetration at reduced B_{c1}

 There exist a surface barrier which prevents vortices from penetrating even above B_{c1}¹

BUT

the surface barrier can be reduced to zero in non-uniform (rough) surfaces²

Surface morphology

Changes in surface barrier

Onset of Q-drop (↑ smoother surfaces)

¹C. Bean and J. D. Livingston, *Phys. Rev. Lett.* 12 p. 14 (1964)

²R. D. Blois and W. de Sorbo, *Phys. Rev. Lett.* 12 p. 499 (1964)

Losses due to flux penetration

 Rabinowitz¹ calculated the power loss due to a normal conducting fluxoid in rf field



$$R_s(B_p) \propto exp(D/B_p)$$

$$D \Box \frac{\Delta}{k_{B}F} \sqrt{\frac{k_{1}}{NRa\ln\left[\left(f-d\right)/a\right]}}$$

 $D \cong 2.2 \text{ T}$ (with $\rho = \rho_n$) $D \cong 5 \div 8 \text{ mT}$ from experiments

Q-drop onset freq. dependence



¹B. Visentin – Frontier Workshop – p. 94
²M. Kelly *et al.* – Frontier Workshop – p. 278
³M. Rabinowitz, *J. Appl. Phys.* 42 p. 88 (1971)

Summary

- The onset field of the Q-drop and the effect of baking seem to depend on the density of grain boundaries
- The Q-drop appears to be driven by magnetic-field
- There is a high oxygen concentration at the oxide/metal interface which seems to be diluted by baking
- An improved oxygen diffusion model can be linked to a change of the onset field for flux penetration to explain the Q-drop and the baking effect

Open issues

- Is there enough experimental evidence to exclude H from playing a role in the Qdrop?
- How can we test the hypothesis of flux penetration during Q-drop?
- Interpretation of experimental data against O hypothesis:
 - Saclay data: Q-drop is not restored after HF rinsing of baked cavity (O conc. near surface restored as before baking)

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